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CONTENTS

Editorial vii
Committees ix
Conference photographs x

Section I. Nuclear reaction analysis and charged-particle activation analysis

Trace-impurity detection by Rutherford backscattering and nuclear resonance reactions
T. Maisch, V. Schüle, R. Günzler, P. Oberschachtsiek, M. Weiser, S. Jans, K. Izsak and S. Kalbitzer 1

Depth profiling of heavy-ion-mixed TiN films
K.P. Lieb, W. Bolse, T. Corts, W. Müller, T. Osipowicz and T. Weber 10

Determination of nitrogen in semiconductor materials using the $^{14}N(p, \alpha)^{11}C$ and $^{14}N(d, n)^{15}O$ nuclear reactions
F. Köhl, J. Krauskopf, P. Misaelides, R. Michelmann, G. Wolf and K. Bethge 19

A simple coincidence method of deuterium profiling using the $D(^3He, \alpha)H$ reaction
M. Wielunski and W. Möller 23

Hydrogen dynamics in electrochromic multilayer systems investigated by the ^{15}N technique
W. Wagner, F. Rauch, C. Ottermann and K. Bange 27

Hydrogen profiling of Nb–Hf–Nb layers by the ^{15}N method
J. Steiger, O. Boebel, M. Briere, A. Weidinger and P. Ziegler 31

Investigations of lattice location and mobility of carbon in GaAs using the channeling technique
A. Mader, J.D. Meyer, P. Thee and K. Bethge 35

Analysis of Cu and O in high-T_c superconductors by 7–9 MeV protons
J. Keinonen and J. Räisänen 39

Determination of ^{18}O concentrations in microsamples of biological fluids
D.D. Cohen, S.D. Bradshaw, F.J. Bradshaw and A. Katsaros 43

An RBS, NRA and SEM study of annealing effects on the microstructure of palladium layers
E. Cereda, G.M. Braga Marcazzan, F. Parmigiani and M. Scagliotti 48

Silicon diffusion in gold grain boundaries studied with a deuteron microbeam
S. Mathot and G. Demortier 52

Thin-layer activation of hip-joint prostheses for tribological tests
W. Neumann, W. Woelfli, P. Heimgartner and R.M. Streicher 57

Trace-element study of glass samples by using activation methods
F. Ditrói, S. Takács, I. Mahunka and Z. Gémesi 62

Charged-particle activation methods for the analysis of carbon and oxygen in high-purity gallium
E.H. Bakraji, A. Giovagnoli, G. Blondiaux and J.-L. Debrun 65

Depth-profiling of beryllium on graphite with ion beams
R. Reichle, R. Behrisch and J. Roth 68

Fluorine profiling after application of various anti-caries gels
H.-E. Zschau, F. Plier, G. Otto, C. Wyrwich and A. Treide 74

Section II. Elastic scattering analysis

Materials analysis using ion beam techniques
D.O. Boerma 77

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(North-Holland)

A low-temperature bolometer for particle detection in Rutherford backscattering analysis
S. Woiwod, R.M. Mueller, B. Stritzker and S.H. Moseley 91

RBS analyses of xenon-irradiated Ti and TiN films
T. Weber, W. Bolse and K.P. Lieb 95

RBS analysis of front contacts for surface-barrier detectors
M.S. Stojanović, M. Milosavljević, K.M. Subotić, F. Boreli, I.H. Wilson and D. Novković 102

Characterization of optical coatings by Rutherford backscattering spectrometry and elastic recoil detection analysis
R. Pretorius and D. Bezuidenhout 105

Influence of electronic charge compensation on Rutherford backscattering spectra of biased insulators
J.D. Meyer and D.E. Arafah 109

RBS investigations of buffer layers between $YBa_2Cu_3O_{7-x}$ and silicon
A. Lubig, C. Buchal, J. Fröhlingsdorf, W. Zander and B. Stritzker 114

Depth distribution of martensite in xenon-implanted stainless steels
A. Johansen, E. Johnson, L. Sarholt-Kristensen, S. Steenstrup, E. Gerritsen, C.J.M. Denissen, H. Keetels, J. Politiek, N. Hayashi and I. Sakamoto 119

Diffusion and strain relaxation in $Si/Si_{1-x}Ge_x/Si$ structures studied with Rutherford backscattering spectrometry
L.J. Van Ijzendoorn, G.F.A. Van de Walle, A.A. Van Gorkum, A.M.L. Theunissen, R.A. Van den Heuvel and J.H. Barrett 127

Investigation of point defects by temperature-dependent dechanneling
G. Götz, K. Gärtner and W. Wesch 131

3D hydrogen profiling by elastic recoil detection analysis in transmission geometry
J. Tirira, P. Trocellier, J.P. Frontier, P. Massiot, J.M. Costantini and V. Mori 135

Investigation of films of $YBa_2Cu_3O_7$ using Rutherford backscattering spectrometry
R.S. Sokhi, P.W. Gilberd and L.G. Earwaker 140

RBS analysis of GaAs and InP after electron beam annealing
G. Roland, H. Baumann and K. Bethge 145

Mass selection and depth profiling by coincident recoil detection for nuclei in the middle mass region
S.S. Klein, P.H.A. Mutsaers and B.E. Fischer 150

Quantitative microanalysis of matrix elements in biological samples by MeV proton scattering
M. Hult and K. Themner 154

Multidimensional ERDA measurements and depth profiling of medium-heavy elements
B. Gebauer, D. Fink, P. Goppelt, M. Wilpert and T.H. Wilpert 159

Time-of-flight spectrometry for materials analysis
T.M. Stanescu, J.D. Meyer, H. Baumann and K. Bethge 167

Thin reference layers available for calibration purposes in ion beam analysis
U. Wätjen, D. Schroyen, E. Bombelka and P. Rietveld 172

Section III. Particle-induced X-ray emission and microbeams

Nuclear microbeams: Realization and use as scientific tool
K. Traxel 177

Accuracy of thick-target micro-PIXE analysis
J.L. Campbell, W.J. Teesdale and J.-X. Wang 189

Nuclear microscopy – elemental mapping using high-energy ion beam techniques
G.W. Grime and F. Watt 197

Materials applications of nuclear microprobes
J.A. Cookson and M.B.H. Breese 208

Proton microprobe studies of the mineralization process in selected organic matrices
E. Rokita, T. Cichocki, S. Divoux, B. Gonsior, M. Höfert, L. Jarczyk, A. Strzalkowski and M. Sych 217

A PIXE mini-beam setup at the Bonn cyclotron for archeometric metal analyses
J. Weber, T. Beier, U. Diehl, D. Lambrecht, H. Mommsen and F.J. Pantenburg 221

Combining PIXE and XRF with gamma-ray transmission to get accurate analysis of archaeological bronzes
M.A. Respaldiza, F. Barranco, J. Gómez-Camacho, B.M. Gómez-Tubío and M.M. Ruiz-Delgado 226

Micro-PIXE analyses of trace elements in black shales from the lower Zechstein copper deposits, Poland
W. Przybyłowicz, H. Kucha, A. Piestrzyński, K. Traxel and S. Bajt 231

PIXE measurements of Kr-sputtered TiN coatings
T. Osipowicz, T. Corts, K.-P. Lieb and F.-J. Bergmeister 238

Determination of the Li/Ni ratio in $Li_xNi_{1-x}O$ thin films by PIXE–PIGE analysis
C. Boni, A. Caridi, E. Cereda, G.M. Braga Marcazzan, F. Parmigiani and M. Scagliotti 243

Seven years of research using the Bruyères Le Châtel microprobe facility: A review
P. Trocellier, M. Mosbah, N. Toulhoat, J. Tirira, J. Gosset, P. Massiot and C. Engelmann 247

Section IV. Accelerator mass spectrometry

Accelerator mass spectrometry: A versatile tool for research
W. Kutschera 252

Applications of accelerator mass spectrometry to electronic materials
J.M. Anthony, S.E. Matteson, D.K. Marble, J.L. Duggan, F.C. McDaniel and D.J. Donahue ... 262

Superconducting minicyclotrons in AMS
K.M. Subotić, D. Novković, M.S. Stojanović and L.S. Milinković 267

Accelerator mass spectrometry with time-of-flight measurement
D. Müller, T. Faestermann, A. Gillitzer, G. Korschinek, R. Scheuer and U. Bittner 271

Accelerator mass spectrometry with fully stripped ^{26}Al, ^{36}Cl, ^{41}Ca and ^{59}Ni ions
H. Faestermann, K. Kato, G. Korschinek, P. Krauthan, E. Nolte, W. Rühm and L. Zerle 275

Measurements of natural concentrations of ^{129}I in uranium ores by accelerator mass spectrometry
E. Boaretto, D. Berkovits, G. Hollos and M. Paul 280

A new AMS beam line at the Erlangen tandem accelerator facility
M. Baumgärtner, U. Emmerling, W. Ernst, E. Finckh, G. Fuchs, F. Gumbmann, M. Haller, R. Höpfl, R. Karschnick, W. Kretschmer, A. Rauscher, M. Schleicher and W. Schuster 286

Section V. Various techniques

Design of a magnetic spectrograph for surface, interface and thin-layer analysis
D.O. Boerma, F. Labohm and J.A. Reinders 291

The Stuttgart positron beam, its performance and recent experiments
W. Bauer, J. Briggmann, H.-D. Carstanjen, S. Connell, W. Decker, J. Diehl, K. Maier, J. Major, H.-E. Schaefer, A. Seeger, H. Stoll and E. Widmann 300

Surface characterization with keV clusters and MeV ions
E.A. Schweikert, M.G. Blain, M.A. Park and E.F. Da Silveira 307

Applications of photonuclear reactions
D.J.S. Findlay 314

Sensitivity of trace-element analysis by X-ray emission induced by 0.1–10 MeV electrons
A.P. Georgiadis, D. Apostolakis, M. Vourkas and A. Pape 321

Research at the positron source TEPOS
F. Ebel, W. Faust, C. Hahn, M. Rückert, H. Schneider, A. Singe and I. Tobehn 328

Electron accelerators at the ENEA Center at Frascati: Development and application
U. Bizzarri, G. Giubileo, G. Messina, L. Picardi, P. Raimondi, C. Ronsivalle, A. Vignati, D. Baraldi, A.M. Castagnola, S. Omarini, L. Fabiani and V. Leoni 331

A synchrotron radiation microprobe for X-ray fluorescence and microtomography at ELETTRA
C. Tuniz, R. Devoti, G. Santoro and F. Zanini 338

On the analysis of neonatal hamster tooth germs with the photon microprobe at Daresbury, UK
G.H.J. Tros, F. Van Langevelde and R.D. Vis 343

Selection of the experimental conditions for white-light SRIXE measurements
W.M. Kwiatek, A.L. Hanson and K.W. Jones 347

Atomic data for accelerator-based X-ray fluorescence spectroscopy
S. Fritzsche, A.M.M. Mohammedein, G. Musiol, I. Reiche, F. Schubert and G. Zschornack 353

Section VI. Ion beam modification

Ion beam modification of metals
G. Dearnaley 358

The formation of compound layers in silicon by ion beam synthesis
K.G. Stephens, K.J. Reeson, B.J. Sealy, R.M. Gwilliam and P.L.F. Hemment 368

Beryllium bombardment for $In_{0.53}Ga_{0.47}As$ and InP photoconductors with picosecond response times
A. Schaelin, R. Loepfe, H. Melchior, M. Suter and W. Woelfli 379

High-dose iron implantation into silicon and metals
G. Müller, G. Klingelhöfer, P. Schwalbach and E. Kankeleit 384

Analysis of annealing and ion implantation effects in Ti/TiN contacts on silicon
M. Milosavljević, N. Bibić, D. Peruško, M.S. Stojanović and I.H. Wilson 391

Production of particle-track membranes by means of a 5 MV tandem accelerator
H.B. Lück, H. Matthes, B. Gemende, B. Heinrich, W. Pfestorf, W. Seidel and S. Turuc 395

Temperature and dose dependences of nitrogen implantation into aluminium
S. Lucas, G. Terwagne and F. Bodart 401

Sputtering yield and residual vacuum influence during titanium implantation into iron
M.A. El Khakani, H. Jaffrezic, G. Marest, N. Moncoffre and J. Tousset 406

Iron-implanted sintered alumina studied by RBS, CEMS and SEM techniques
C. Donnet, H. Jaffrezic, G. Marest, N. Moncoffre and J. Tousset 410

Ion beam mixing of titanium films on stainless steel
W. Bolse, T. Weber and W. Lohmann 416

The irradiation laboratory at ČKD Semiconductors Praha
V. Kliský 420

Diffusion and corrosion behaviour of tungsten-implanted aluminium and the $Al_{12}W$ phase
R.C. Da Silva, M.F. Da Silva, A.A. Melo, J.C. Soares, E. Leitão and M. Barbosa 423

Determination of lattice sites for Eu, Hf and Nd in $LiNbO_3$ by RBS/channeling experiments
L. Rebouta, J.C. Soares, M.F. Da Silva, J.A. Sanz-Garcia, E. Diéguez and F. Agulló-López 428

Argon irradiation damage at a Cu/Al_2O_3 interface for different alumina structures
M. El Bouanani, A. Chevarier, N. Chevarier, E. Gerlic, H. Jaffrezic and M. Stern 431

Angular dependence of the self-ion-sputtering yield of silicon at 30 keV
O. Fröhlich, H. Baumann and K. Bethge 436

PECVD Si nitride and Si oxide layers – hydrogen analysis and etching after ion implantation
C. Neelmeijer, B. Schmidt, W. Rudolph, H. Münzer, D. Grambole, C. Heiser and F. Herrmann . 439

Section VII. Accelerator development

Recent developments in ion implantation accelerators
R.W. Thomae 444

A new generation of single-ended Van de Graaff accelerators for ion implantation and ion beam analysis
H.A.P. Van Oosterhout 455
RFQ accelerators for ion implantation
A. Schempp 460
A standing-wave structure for a synchrotron ring injector
J.-P. Labrie 465
Energy control of the IMPELA™ series of industrial accelerators
G. Hare, S. Craig, J.-P. Labrie, C.B. Lawrence, J. Ungrin and B. White 470
A 3 MV Tandetron facility at KFUPM
H.A. Al-Juwair, M.M. Al-Kofahi, A.B. Hallak and M. Rajeh 474
An ECR–RFQ ion beam facility for materials research with highly charged slow ions
D. Hofmann, H. Baumann, C. Freudenberger, R. Herrmann, A. Schempp, H. Schmidt-Böcking, G. Zschornack, K. Bethge, H. Klein, C. Lyneis and R. Stock 478

Author Index 481